

DO NOT ENTER: /M.A./

06/04/2008

DOCKET NO: 263788US2PCT

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :  
KEISUKE KAWAMURA, ET AL. : EXAMINER: ARANCIBIA, M. G.  
SERIAL NO: 10/519,475 :  
FILED: DECEMBER 28, 2004 : GROUP ART UNIT: 1792  
FOR: APPARATUS FOR PLASMA :  
PROCESSING, METHOD OF :  
PROCESSING SUBSTRATE :  
THEREWITH, APPARATUS FOR :  
PLASMA-ENHANCED CHEMICAL :  
VAPOR DEPOSITION, AND METHOD :  
FOR FILM FORMATION THEREWITH

AMENDMENT UNDER 37 C.F.R. § 1.116

COMMISSIONER FOR PATENTS  
ALEXANDRIA, VIRGINIA 22313

SIR:

In response to the Office Action dated January 29, 2008, please amend the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 8 of this paper.